

## Computational Imaging for Correction of non-isoplanatic Aberrations in Optical Wafer Metrology

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MathMet 2022  
Session-2  
13:20-13:40



# Optical Wafer Metrology and *Holistic Patterning* in Lithography

## Optical Lithography

Scanner with advanced control capability



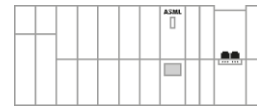
Resist



Mask



DUV



EUV. NA=0.33 =>0.55

## DUV- and EUV Scanners

IMAGE

MODEL

MEASURE



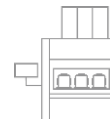
Computational  
Lithography



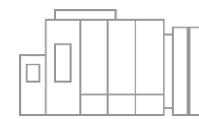
Metrology



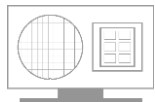
Optical and e-beam  
metrology and inspection



YieldStar



E-beam



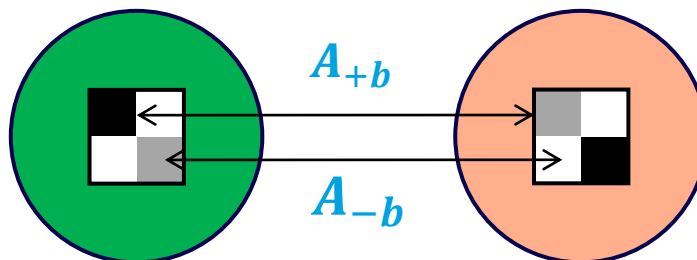
Deep Learning Algorithms

# Optical Metrology : diffraction-based overlay metrology (DBO)

YieldStar



Set of 4 intensities yields overlay

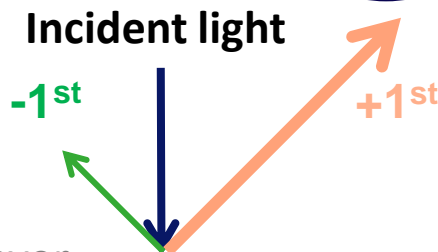


Diffraction Asymmetries

$$I_{+b}^{+1} - I_{+b}^{-1} = A_{+b}$$

$$I_{-b}^{+1} - I_{-b}^{-1} = A_{-b}$$

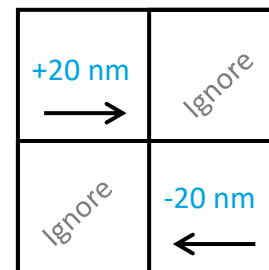
measured  $\pm 1^{\text{st}}$  order diffraction intensities



Grating in top layer

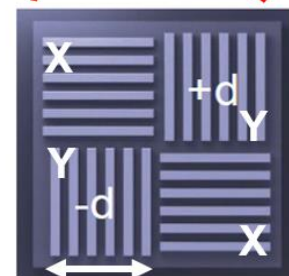
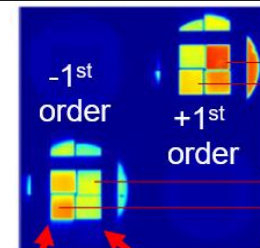


Grating in bottom layer



$\mu$ DBO target on Wafer  
10x10  $\mu\text{m}^2$

Dark-Field Image

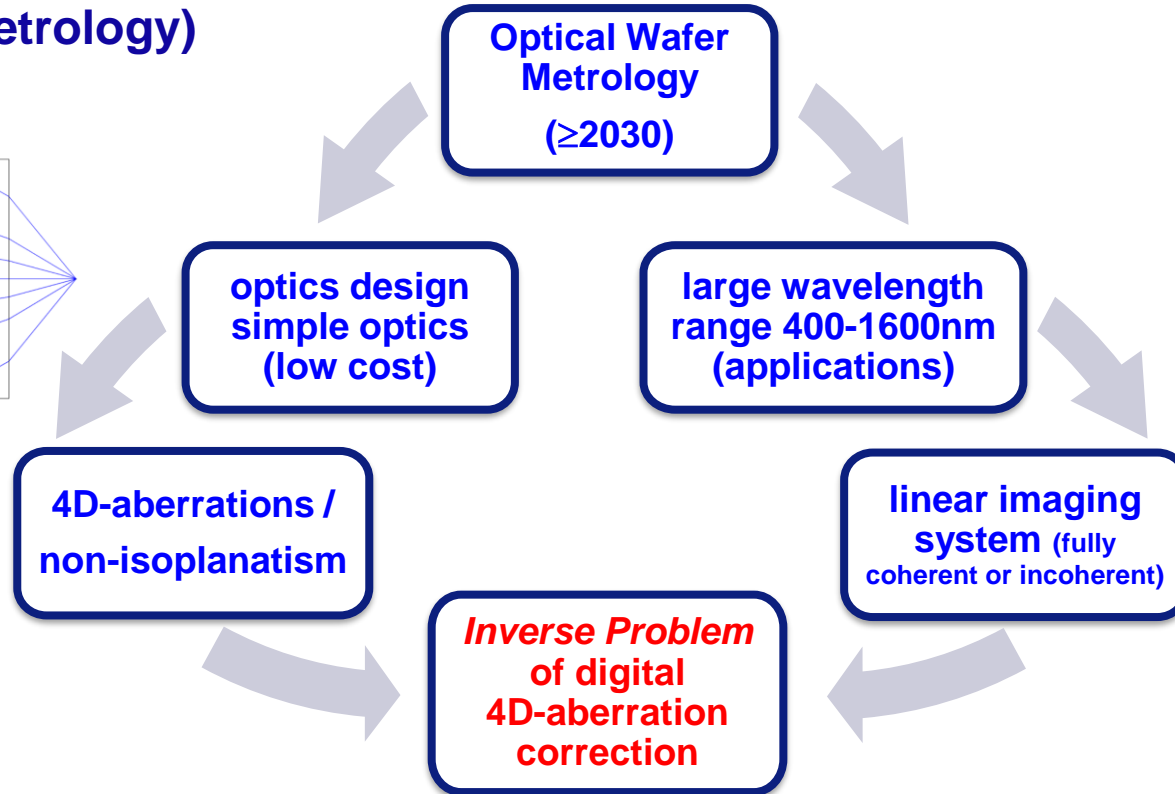
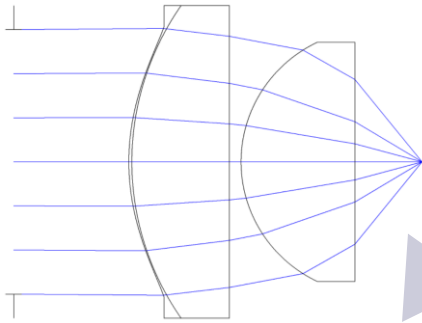


Target-on-Wafer

DBO diffraction-based overlay (metrology)  
 $\mu$ DBO small-target DBO  
OV overlay

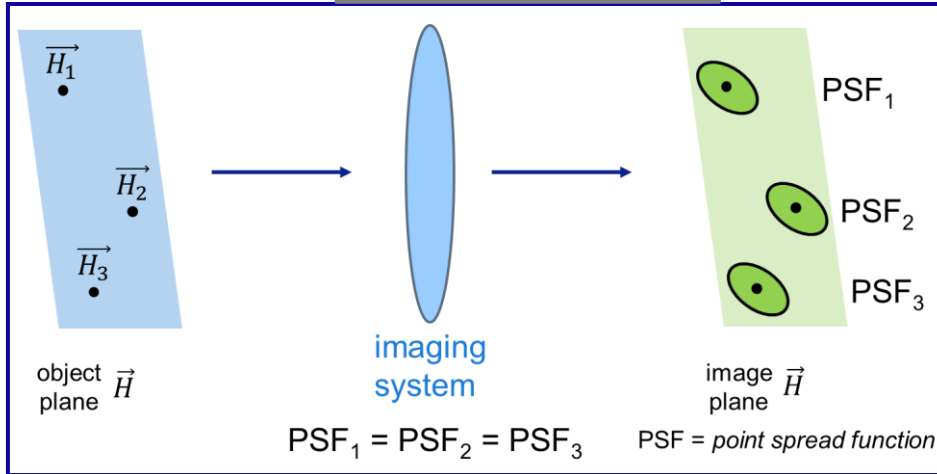
ASML

# Some Views on Our Research Landscape (for wafer metrology)



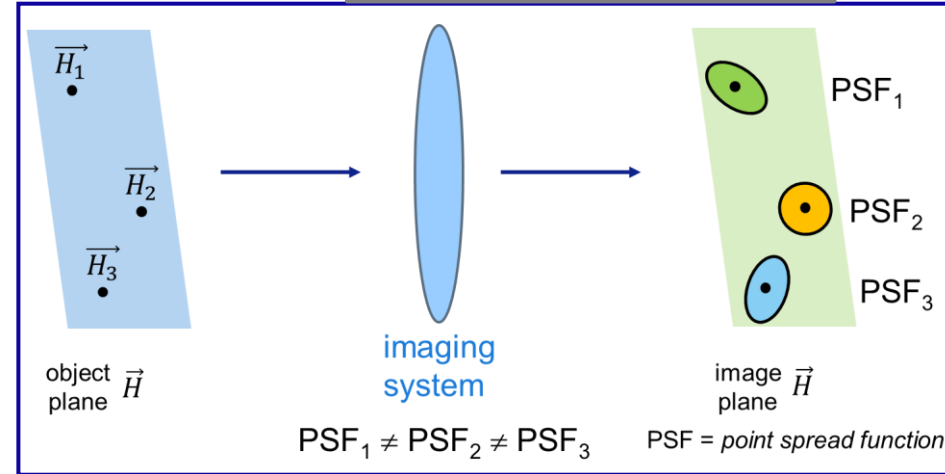
# 2D-aberrations versus 4D-aberrations (isoplanatic versus non-isoplanatic)

## 2D / isoplanatic



PSF is constant over the field

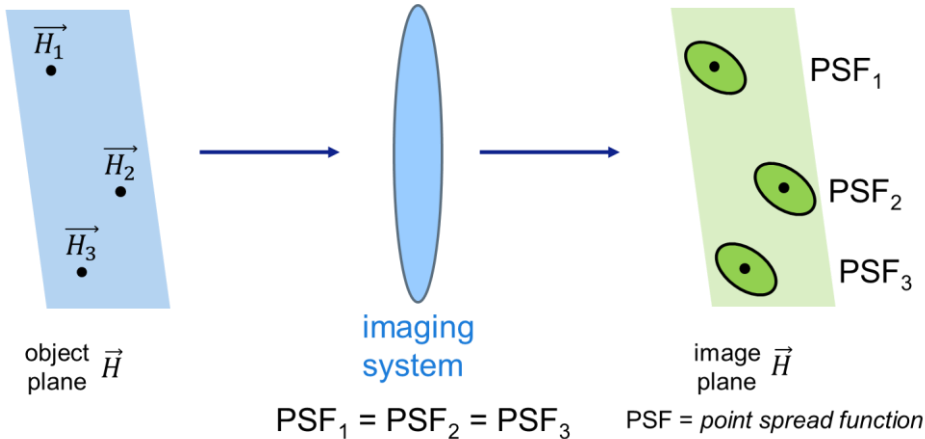
## 4D / non-isoplanatic



PSF depends on field-position

# 2D-aberrations versus 4D-aberrations (isoplanatic versus non-isoplanatic)

## 2D / isoplanatic



$H$  field space  
(real space)

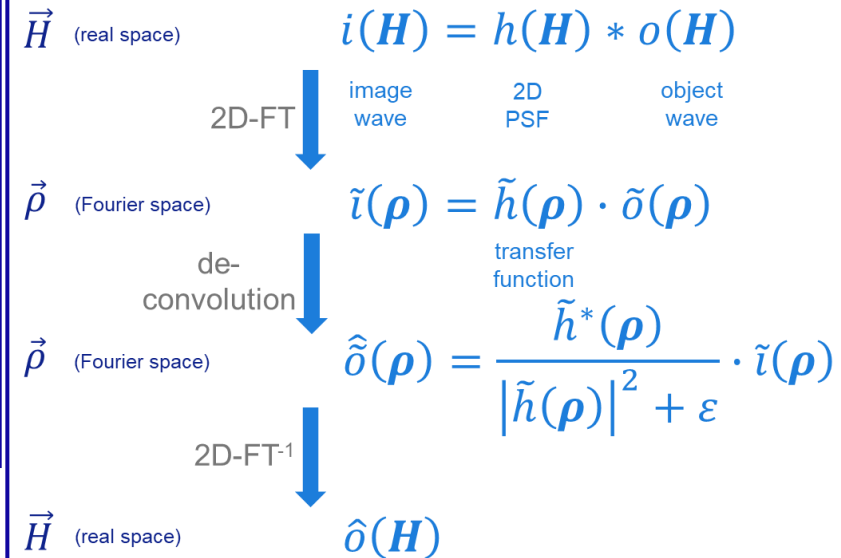
$\rho$  pupil space  
(Fourier space)

$$\tilde{h}(\rho) = A(\rho) e^{iW(\rho)}$$

transfer function      aperture function      wave aberration function

Zernike expansion

## Isoplanatic Computational Imaging



**! NOT POSSIBLE in case of Non-Isoplanatic Imaging !**  
since  $W_{\text{non-isopl}} = W(\rho, H)$  Hopkins expansion

# Hopkins' Expansion of 4D wave-aberration function (rotationally symmetric system)

$\vec{H}$  field  
(real space)

$\vec{\rho}$  pupil  
(Fourier space)



Hopkins  
(1918-1994) <sup>2</sup> (Hopkins coefficients;

J. Sasian Table 5.1)

$$(H^2)^j (\vec{H} \cdot \vec{\rho})^m (\rho^2)^n$$

Aberration name	Vector form	Algebraic form	$j$	$m$	$n$
<i>Zero order</i>					
Uniform piston	$W_{000}$	$W_{000}$	0	0	0
<i>Second order</i>					
Quadratic piston	$W_{200}(\vec{H} \cdot \vec{H})$	$W_{200}H^2$	1	0	0
Magnification	$W_{111}(\vec{H} \cdot \vec{\rho})$	$W_{111}H\rho \cos(\phi)$	0	1	0
Focus	$W_{020}(\vec{\rho} \cdot \vec{\rho})$	$W_{020}\rho^2$	0	0	1
<i>Fourth order</i>					
Spherical aberration	$W_{040}(\vec{\rho} \cdot \vec{\rho})^2$	$W_{040}\rho^4$	0	0	2
Coma <i>pupil distortion</i>	$W_{131}(\vec{H} \cdot \vec{\rho})(\vec{\rho} \cdot \vec{\rho})$	$W_{131}H\rho^3 \cos(\phi)$	0	1	1
Astigmatism	$W_{222}(\vec{H} \cdot \vec{\rho})^2$	$W_{222}H^2\rho^2 \cos^2(\phi)$	0	2	0
Field curvature	$W_{220}(\vec{H} \cdot \vec{H})(\vec{\rho} \cdot \vec{\rho})$	$W_{220}H^2\rho^2$	1	0	1
Distortion <i>field distortion</i>	$W_{311}(\vec{H} \cdot \vec{H})(\vec{H} \cdot \vec{\rho})$	$W_{311}H^3\rho \cos(\phi)$	1	1	0
Quartic piston	$W_{400}(\vec{H} \cdot \vec{H})^2$	$W_{400}H^4$	2	0	0
<i>Sixth order</i>					
Oblique spherical aberration	$W_{240}(\vec{H} \cdot \vec{H})(\vec{\rho} \cdot \vec{\rho})^2$	$W_{240}H^2\rho^4$	1	0	2
Coma	$W_{331}(\vec{H} \cdot \vec{H})(\vec{H} \cdot \vec{\rho})(\vec{\rho} \cdot \vec{\rho})$	$W_{331}H^3\rho^3 \cos(\phi)$	1	1	1
Astigmatism	$W_{422}(\vec{H} \cdot \vec{H})(\vec{H} \cdot \vec{\rho})^2$	$W_{422}H^4\rho^2 \cos^2(\phi)$	1	2	0
Field curvature	$W_{420}(\vec{H} \cdot \vec{H})^2(\vec{\rho} \cdot \vec{\rho})$	$W_{420}H^4\rho^2$	2	0	1
Distortion	$W_{511}(\vec{H} \cdot \vec{H})^2(\vec{H} \cdot \vec{\rho})$	$W_{511}H^5\rho \cos(\phi)$	2	1	0
Piston	$W_{600}(\vec{H} \cdot \vec{H})^3$	$W_{600}H^6$	3	0	0
Spherical aberration	$W_{060}(\vec{\rho} \cdot \vec{\rho})^3$	$W_{060}\rho^6$	0	0	3
Un-named	$W_{151}(\vec{H} \cdot \vec{\rho})(\vec{\rho} \cdot \vec{\rho})^2$	$W_{151}H\rho^5 \cos(\phi)$	0	1	2
Un-named	$W_{242}(\vec{H} \cdot \vec{\rho})^2(\vec{\rho} \cdot \vec{\rho})$	$W_{242}H^2\rho^4 \cos^2(\phi)$	0	2	1
Un-named	$W_{333}(\vec{H} \cdot \vec{\rho})^3$	$W_{333}H^3\rho^3 \cos^3(\phi)$	0	3	0

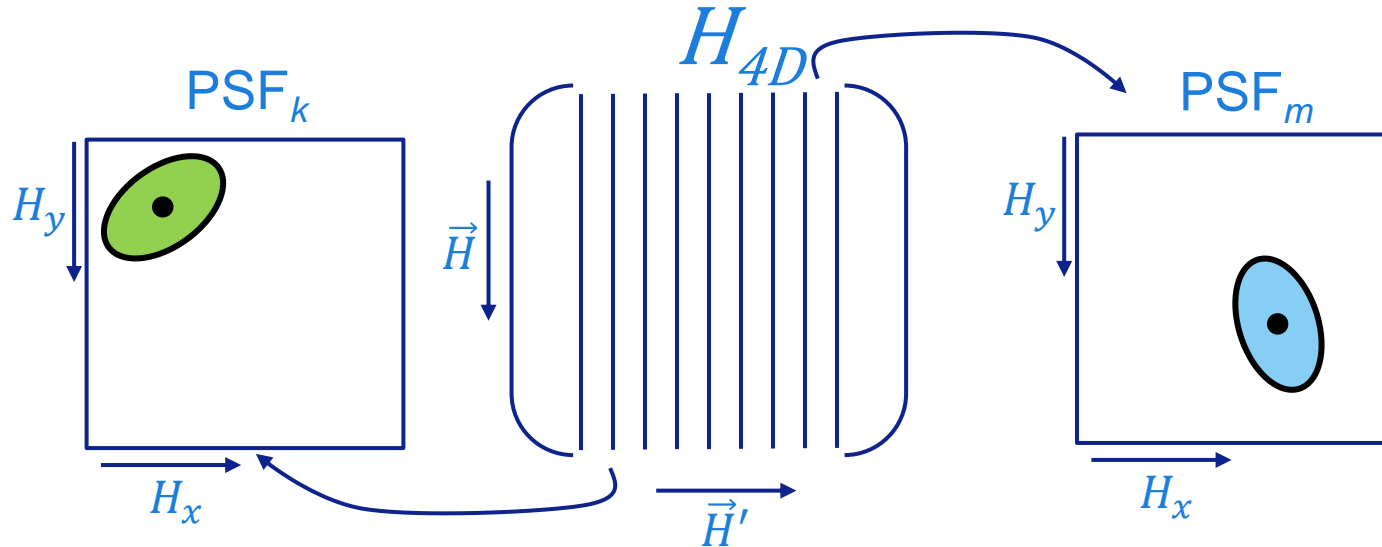
# Non-isoplanatic 4D-PSF Forward Model

$$i(\vec{H}) = \int_{4D-PSF} H_{4D}(\vec{H}; \vec{H}') o(\vec{H}') d\vec{H}'$$

image wave
4D-PSF
object wave

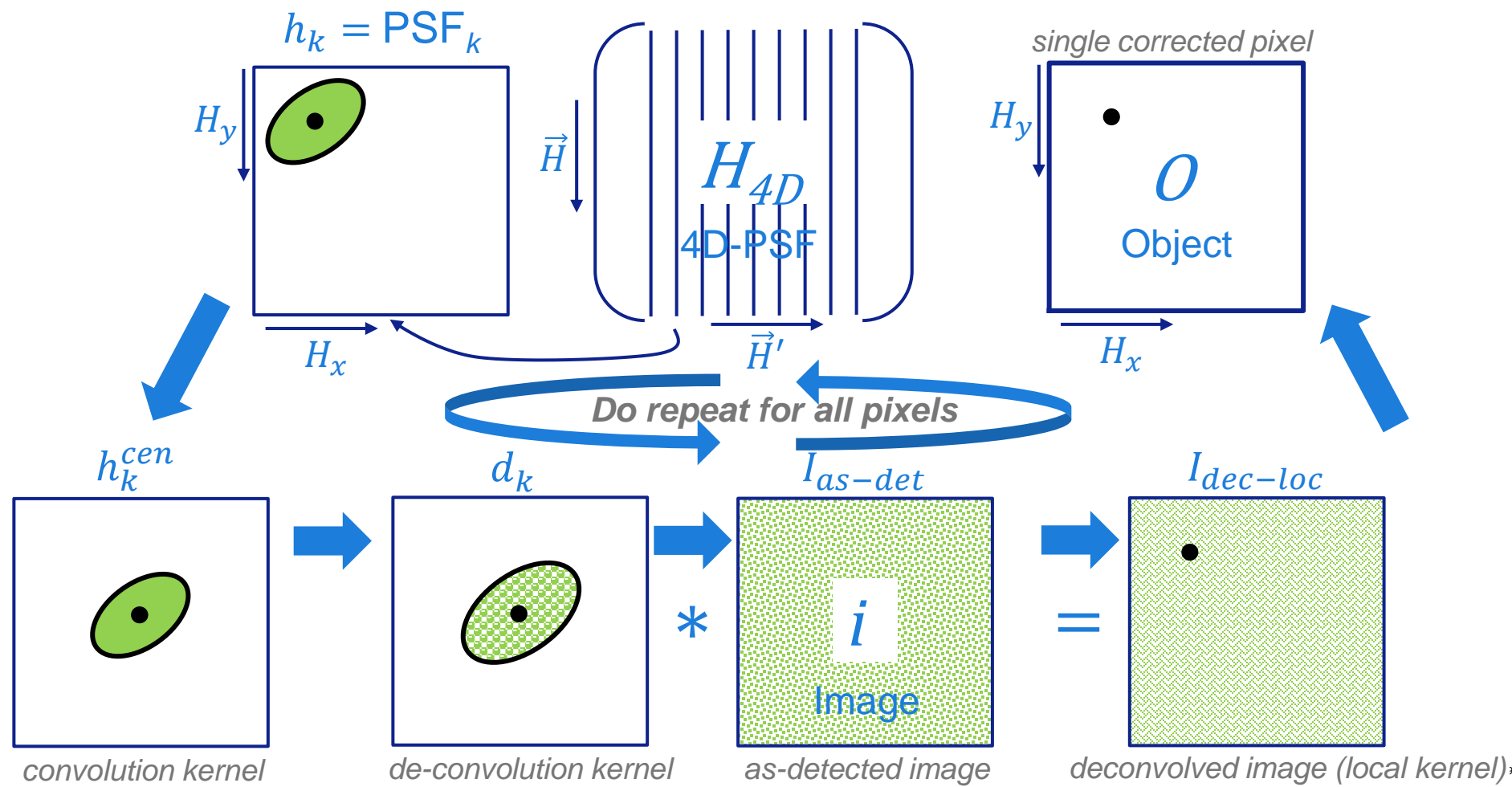
matrix notation

$$\vec{i} = H_{4D} \cdot o$$

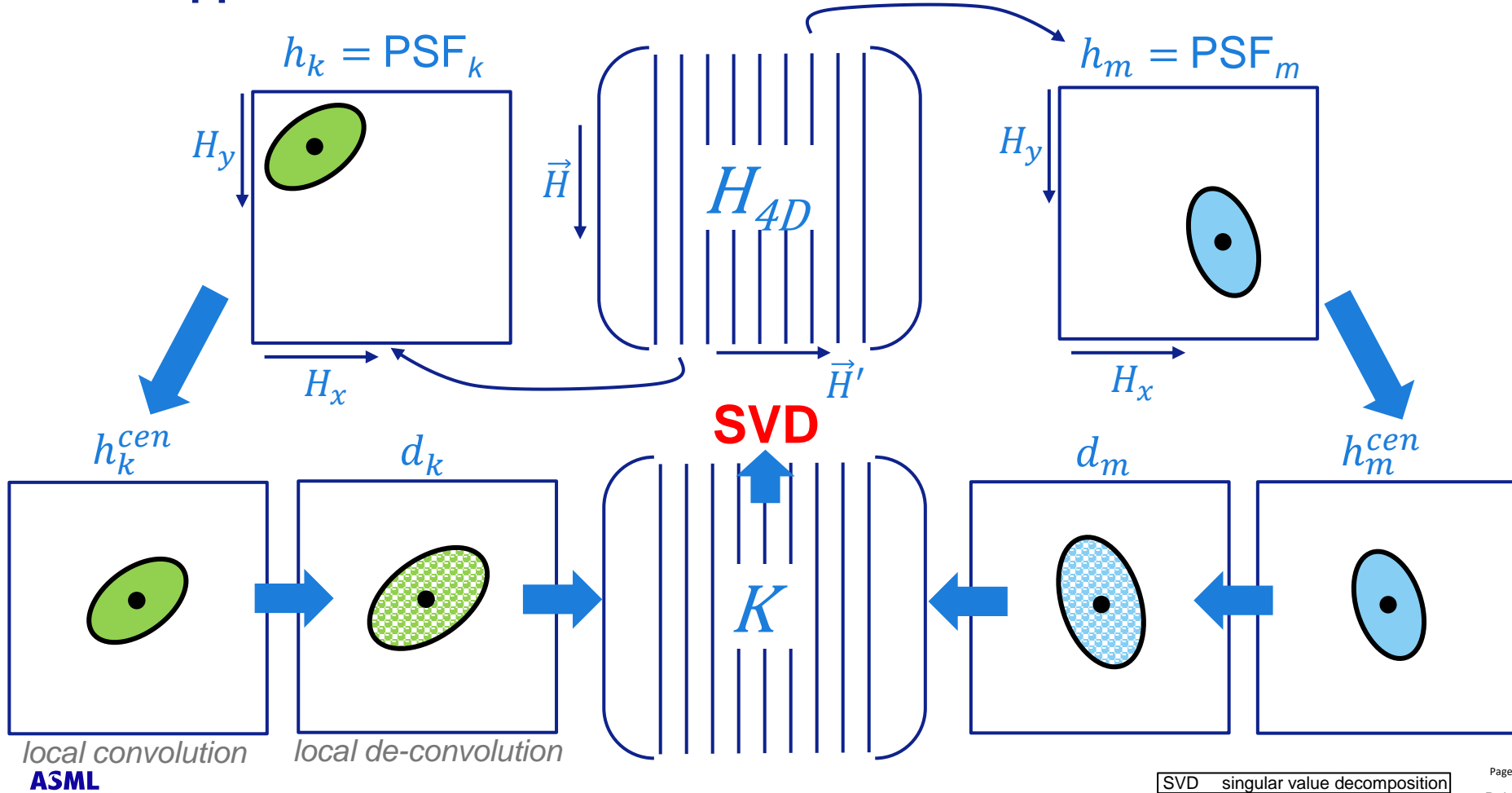




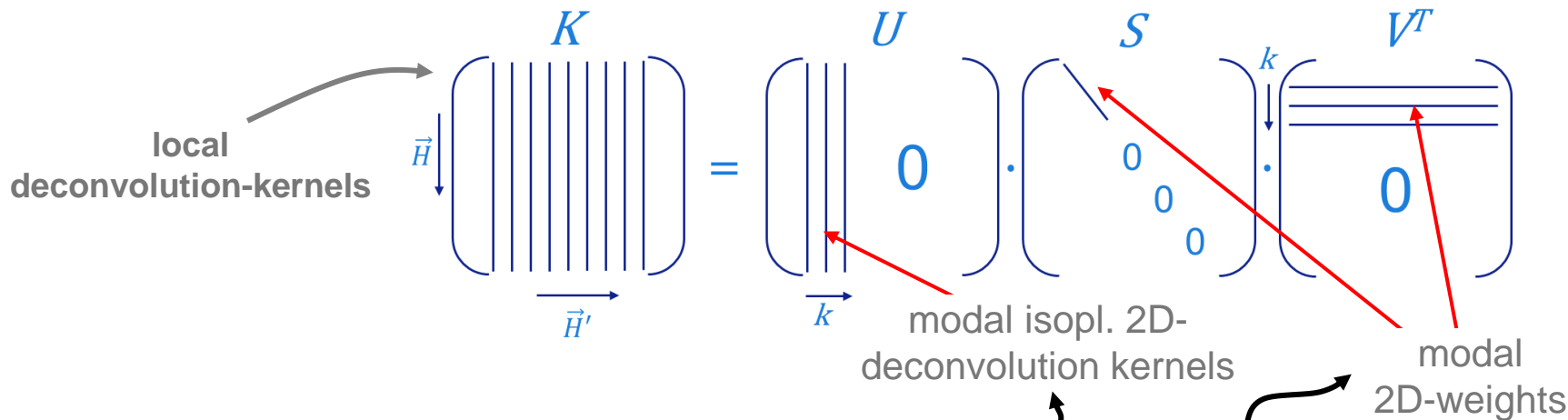
# Concept of *Point-per-Point-Deconvolution* for solution of Inverse Problem



# New Approach: SVD-on-Deconvolution-Kernels for Inverse Problem



# New Approach: SVD-on-Deconvolution-Kernels for Inverse Problem



product-convolution  
series approximation  
of 4D-Deconvolution Kernels

$$D_{4D}(\vec{H}; \vec{H}') \approx \sum_{k=1}^{k_{\max}} p_k(\vec{H} - \vec{H}') w_k(\vec{H}')$$

SVD-based  
deconvolution  
for 4D-aberrations  
( $\sim k_{\max}$  FFTs)

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$$\hat{o}(\vec{H}) \approx \sum_{k=1}^{k_{\max}} p_k(\vec{H}) * [w_k(\vec{H}) i(\vec{H})]$$

object-field

image-field

$k_{\max}$  isoplanatic modal  
deconvolutions on spatially  
weighted versions of the  
measured image field  $i$ .

## Two Strategies for 4D Aberration Correction

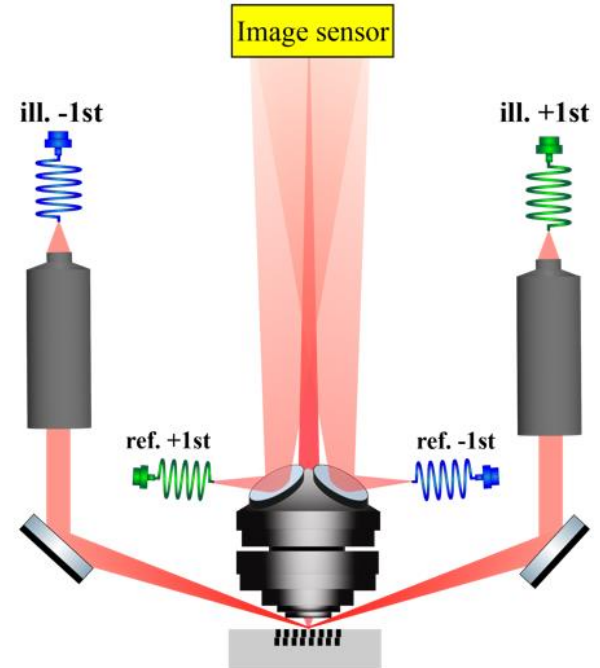
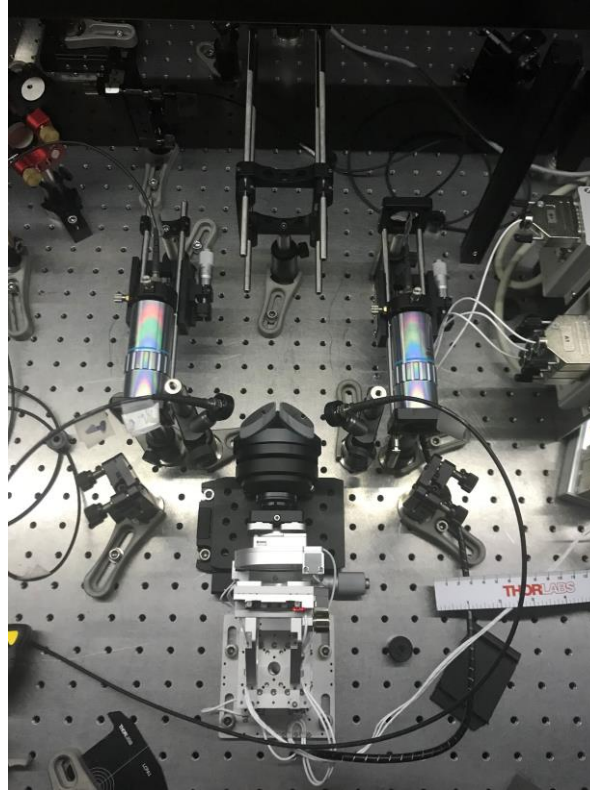
Strategy-1 1-step Approach	Strategy-2 3-step Approach
1. <b>SVD-based Deconvolution</b> for all 2D & 4D aberrations in one go.	1. <b>Isoplanatic Deconvolution</b> with the deconvolution kernel for the PSF at one chosen location.
-	2. <b>Pupil Distortion Correction</b> (by <i>remapping</i> of pupil (Fourier) space due to W131, W151, ...)
-	3. <b>SVD-based Deconvolution</b> for all remaining 4D aberrations.
<b>PRO</b> One single framework	<b>PRO</b> Computational efficiency

# Dark-Field Holographic Microscope (DHM)

Experimental  
DHM set-up  
@ VU-ARCNL

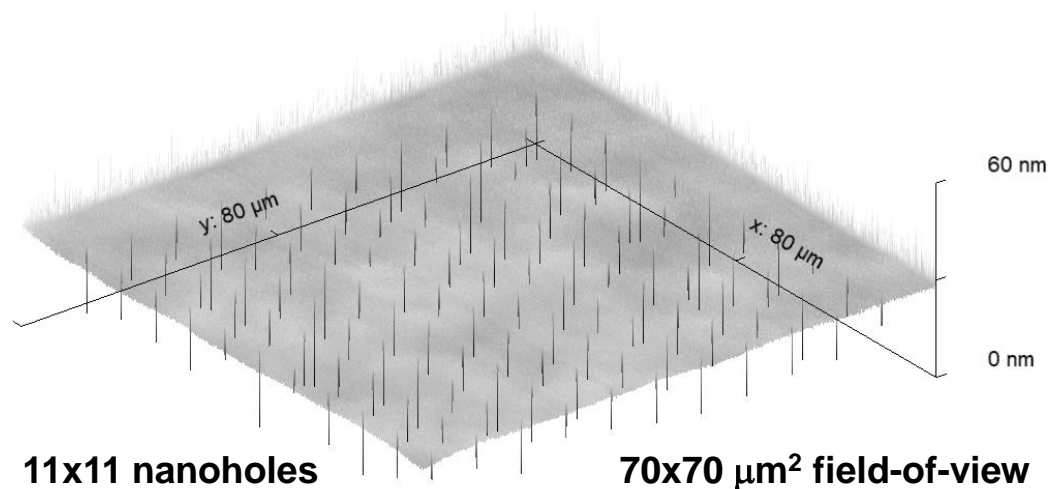
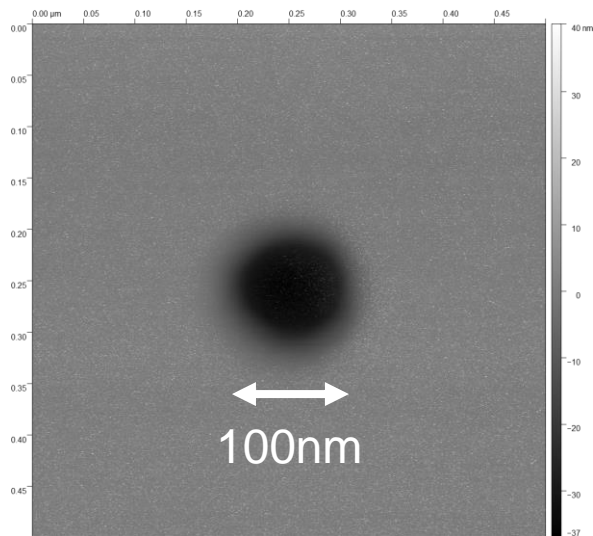
$\lambda = 532\text{nm} / 632\text{nm}$   
NA = 0.80

- off-axis holography
- measurement of amplitude and phase of the image field from the *sideband* of the hologram

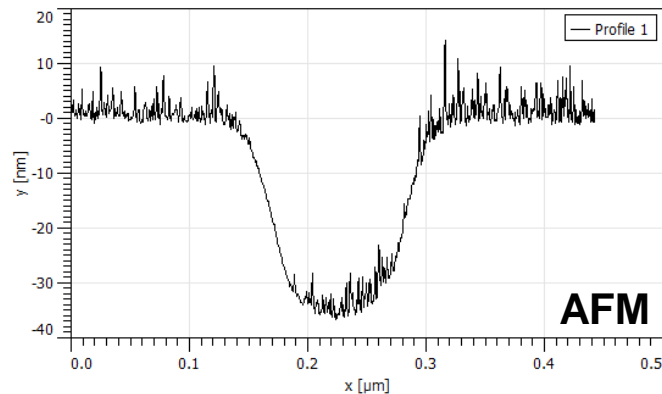


Schematics of  
DHM set-up  
@ VU-ARCNL

# 4D-PSF Calibration via 2D-array of Nanoholes

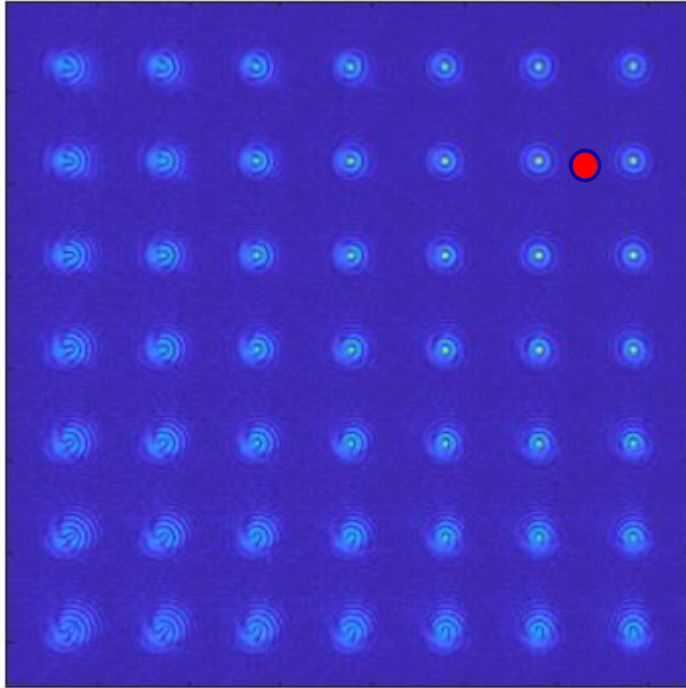


- Nanoholes acts as  $\delta$ -functions
- Nanoholes probe the spatial variation of the 4D-PSFs as measured directly via the sideband of the hologram.



# 4D-PSF Calibration via 2D-array of Nanoholes

Measured PSFs



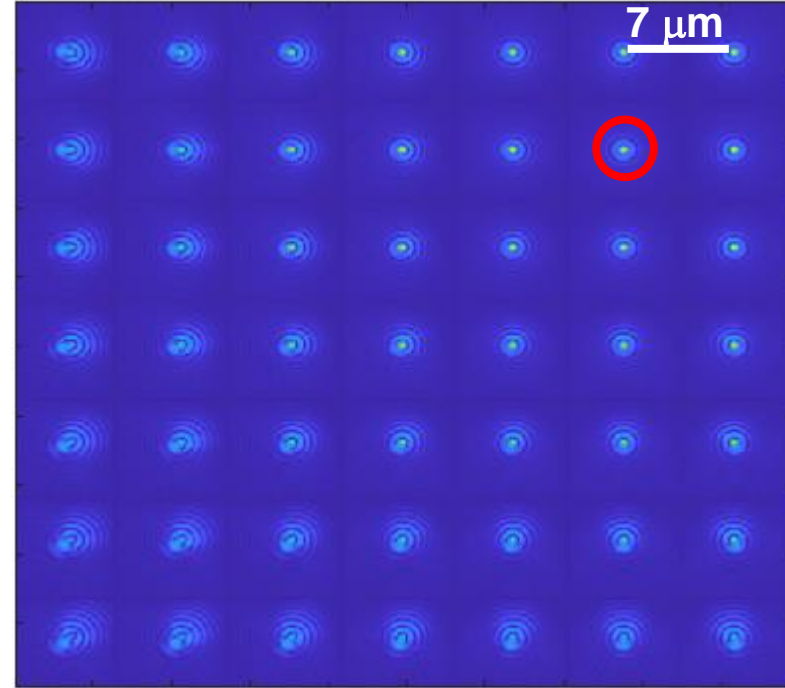
$\lambda = 532\text{nm}$   
 $\text{NA} = 0.80$



assumed position  
of *nodal point*  
(= origin of field space)

Simulated PSFs (from parameters Optics Design)

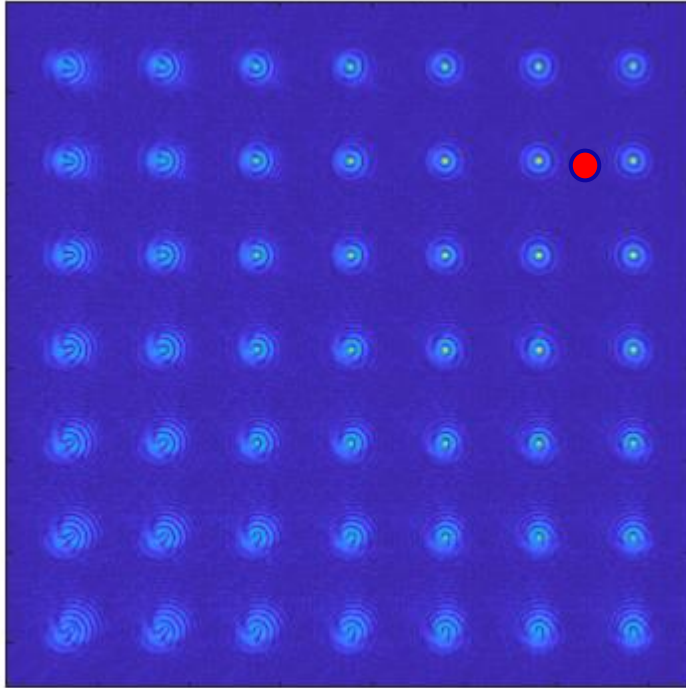
abs all 11x11 PSFs at 532nm at 7 $\mu\text{m}$  distance



7x7 SW-subset of 11x11 nanohole array

# 4D-PSF Calibration via 2D-array of Nanoholes

Measured PSFs



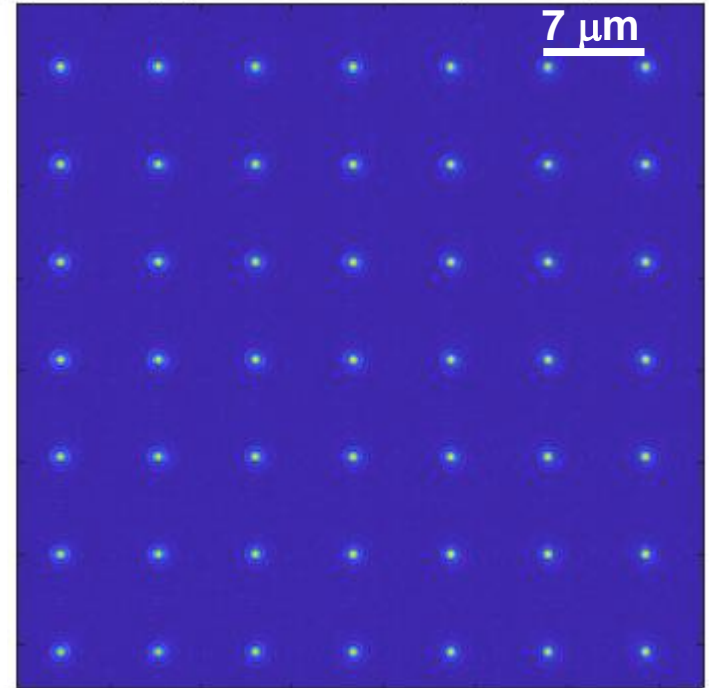
$\lambda = 532\text{nm}$

NA = 0.80



assumed position  
of *nodal point*  
(= origin of field space)

Isoplanatic+pupil distortion+SVD (4 modes) correction

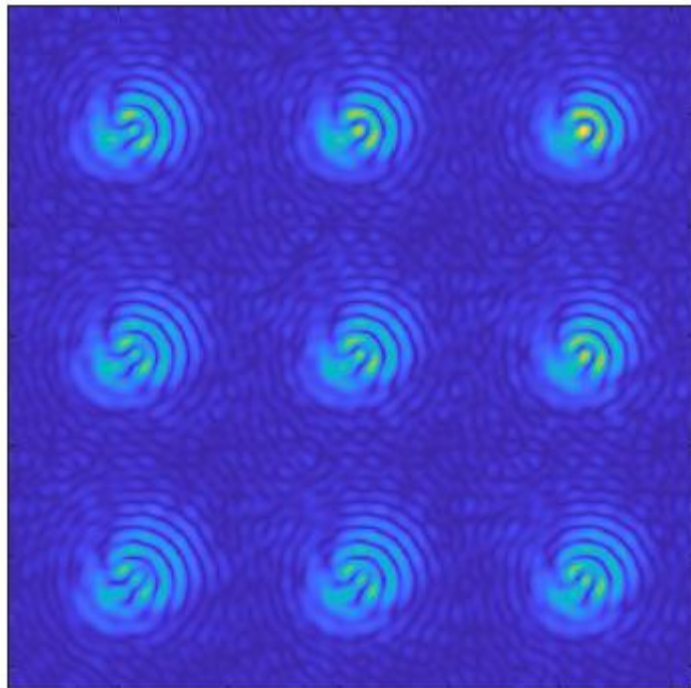


7x7 SW-subset of 11x11 nanohole array

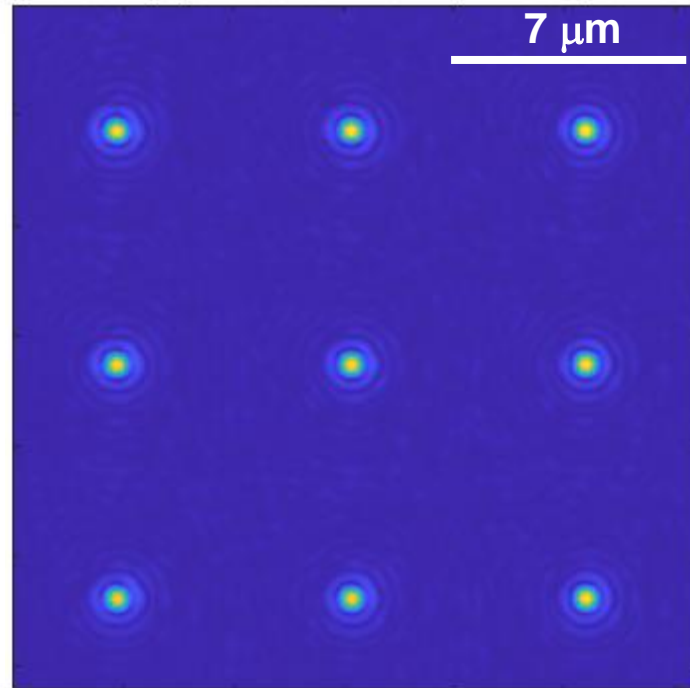


# 4D-PSF Calibration via 2D-array of Nanoholes

Measured PSFs



Isoplanatic+pupil distortion+SVD (4 modes) correction

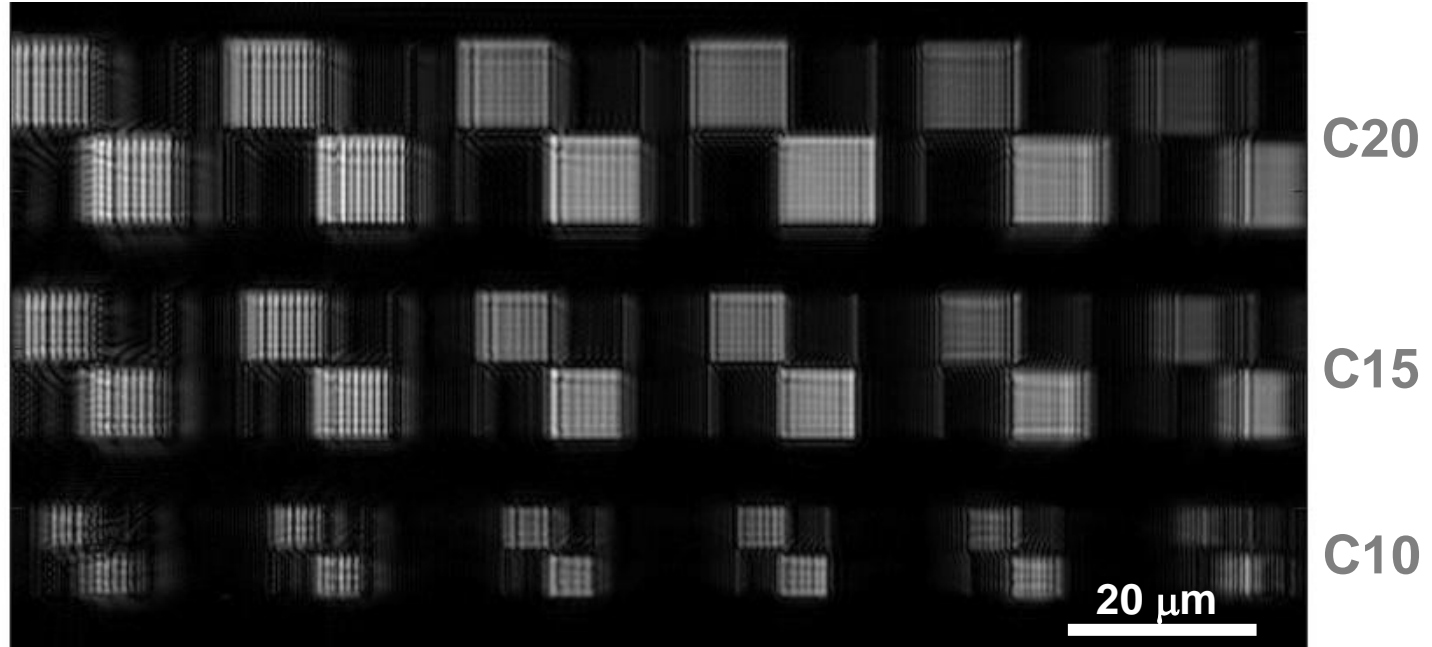


$\lambda = 532\text{nm}$   
NA = 0.80

# 4D Aberration Correction for Array of Grating Pads

No Correction, *as-detected*.

$\lambda = 632\text{nm}$   
NA = 0.80

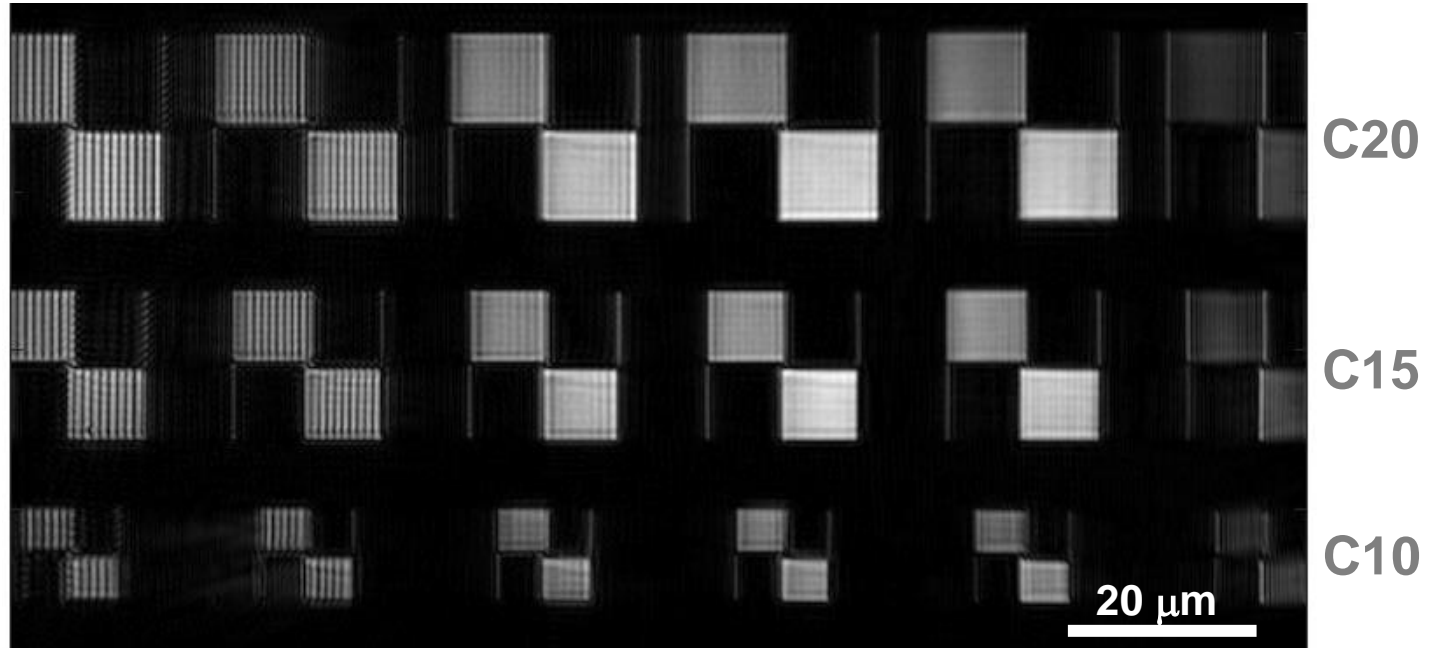


itches: 900nm 800nm 700nm 600nm 500nm 400nm

# 4D Aberration Correction for Array of Grating Pads

Full Correction, isopl. + pupil disto.corr. + SVD + *digital focus*.

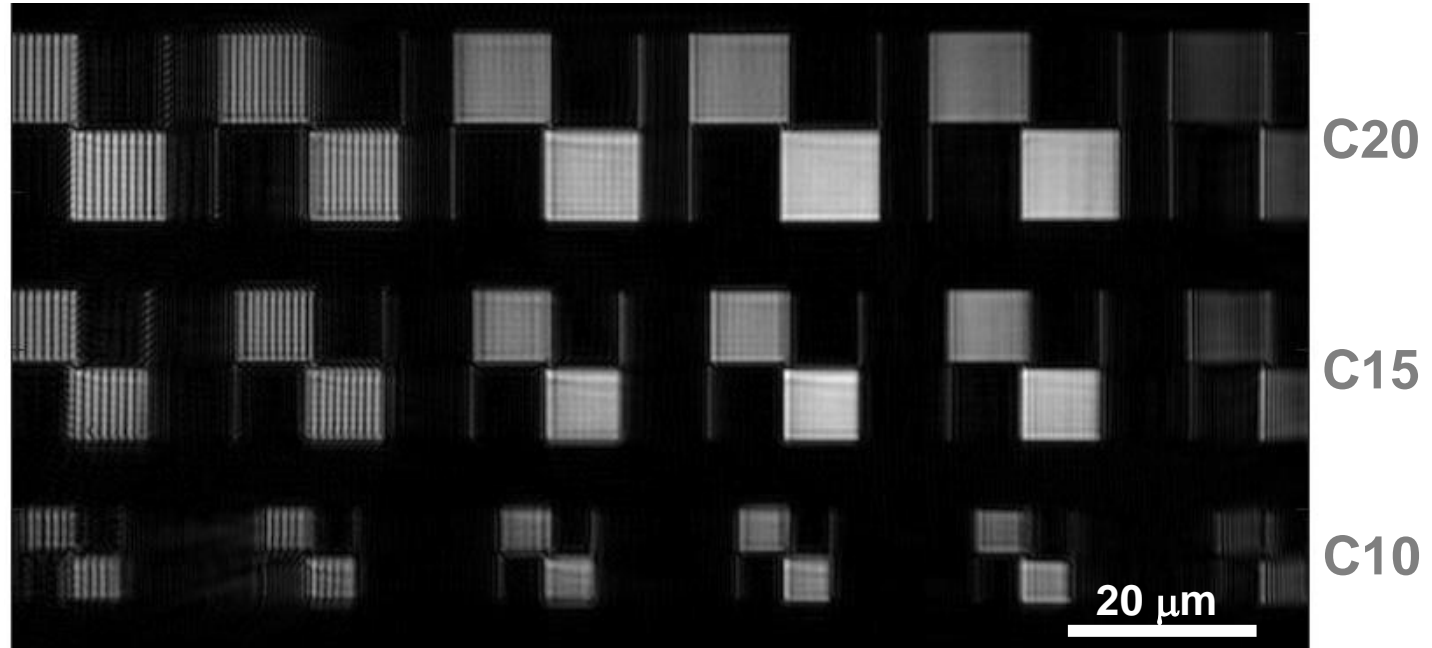
$\lambda = 632\text{nm}$   
NA = 0.80



# 4D Aberration Correction for Array of Grating Pads

Full Correction, isopl. + pupil disto.corr. + SVD + *NO digital focus.*

$\lambda = 632\text{nm}$   
NA = 0.80



## Some Extra Thoughts

- Non-isoplanatism can be caused by at least 3 effects:
  - 4D aberrations of the imaging optics
  - *Surface roughness* of the multiple lens components
  - *Field-position dependent apodization* in Holographic Microscopy, see submitted paper to Optics Express (Sept. 2022):

**Field-position dependent apodization in dark-field Digital Holographic Microscopy for semiconductor metrology**

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- Other areas of Application:
  - Correction for Spatially Varying Blur in **Incoherent Imaging** in Astronomy
    - See: L. Denis, E. Thiebaut, F. Soulez, J.-M. Becker, R. Mourya, *Fast Approximations of Shift-Variant Blur*, Int. J. Comput. Vis. Vol. 115, 2015, pp. 253-278
    - Based on MSE-optimization using an **iterative approach**

# Conclusions

- Deconvolution for 4D field-dependent non-isoplanatic aberrations is feasible for coherent imaging in off-axis holography at low computational costs.
- A computationally efficient SVD-based deconvolution strategy has been proposed.
- The SVD-based deconvolution can be combined with two prior steps of
  - (a) isoplanatic deconvolution
  - (b) pupil distortion correctionin order to further increase computational efficiency.
- Very first experimental data as acquired with Dark-Field Holographic Microscopy have shown a first proof of concept of our 4D aberration correction strategy.

**Thank  
you!**



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Veldhoven